

100 200 300 400 500 600 700 800 900 1000



Remote Bias Electrostatic Force Microscopy: Seeing the Invisible

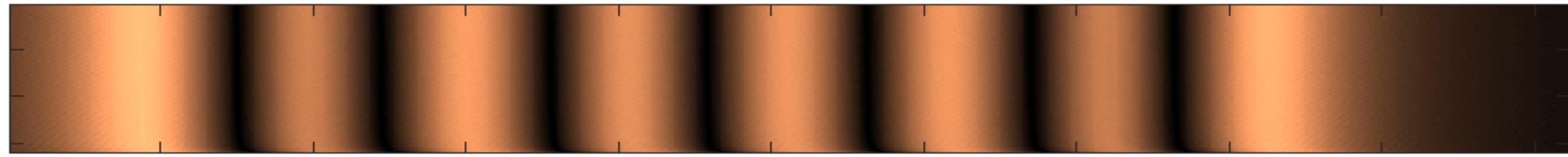
Joseph Tibbs

SPS NIST Research Intern

August 2nd, 2019

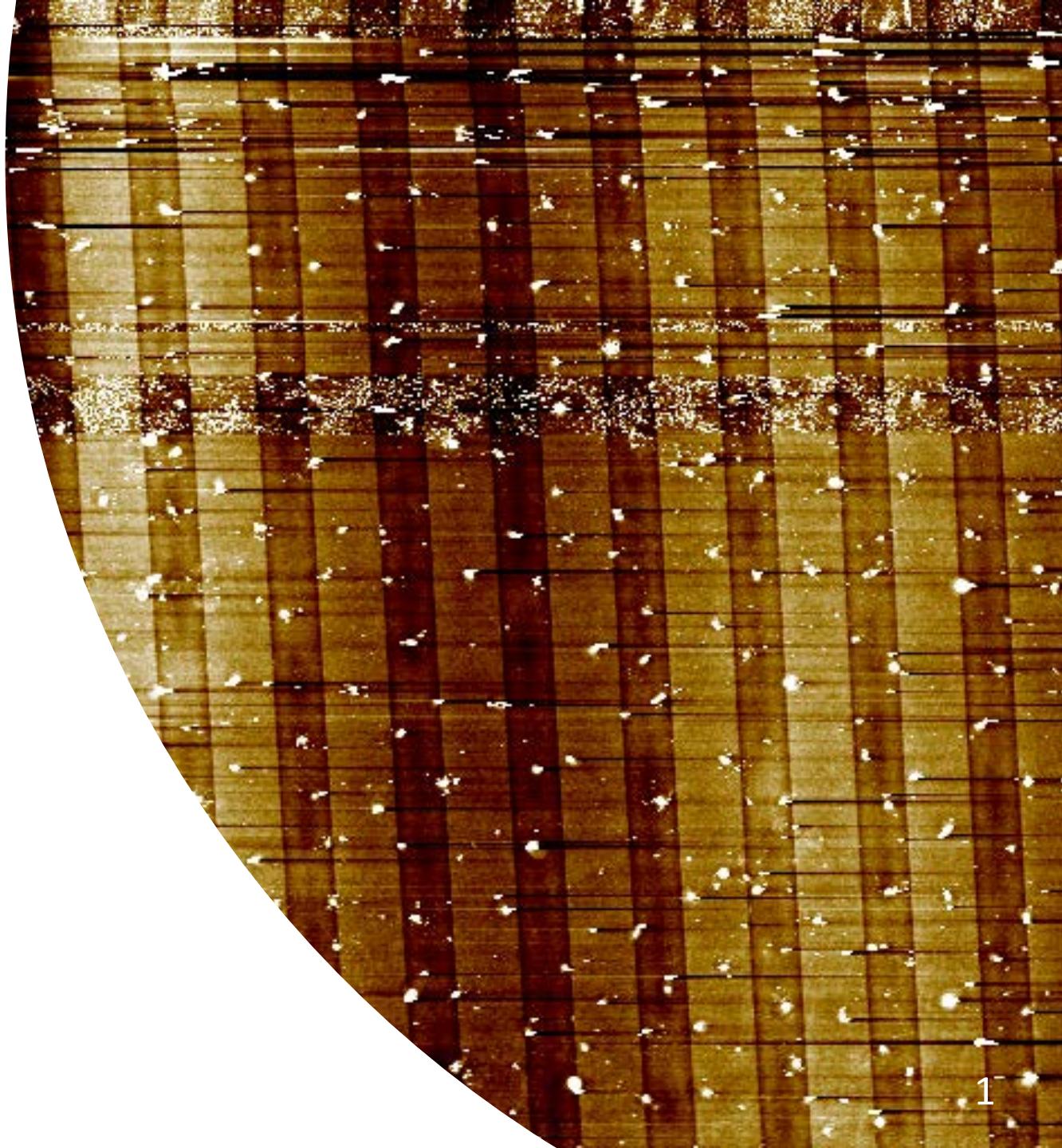
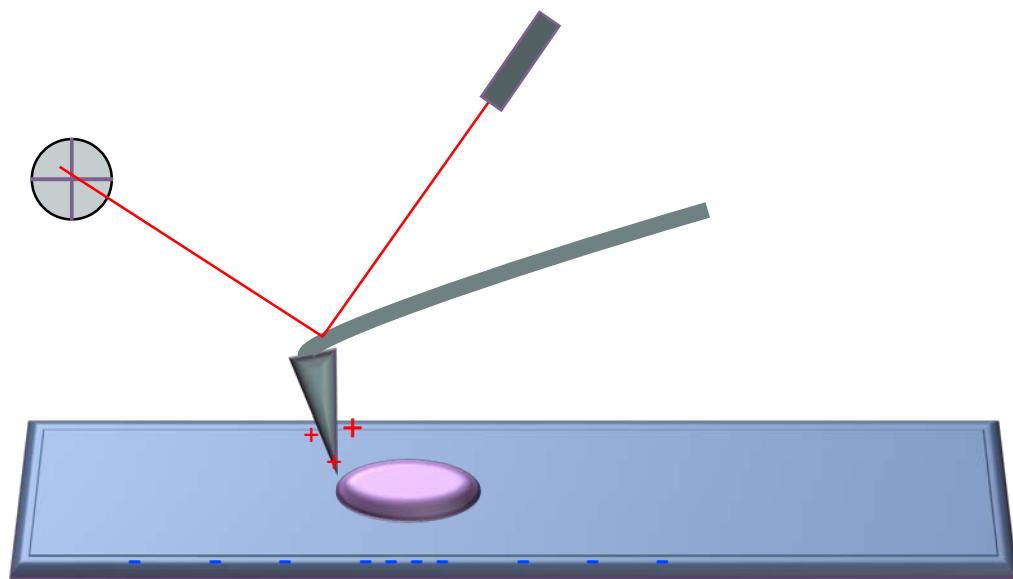


100 200 300 400 500 600 700 800 900 1000



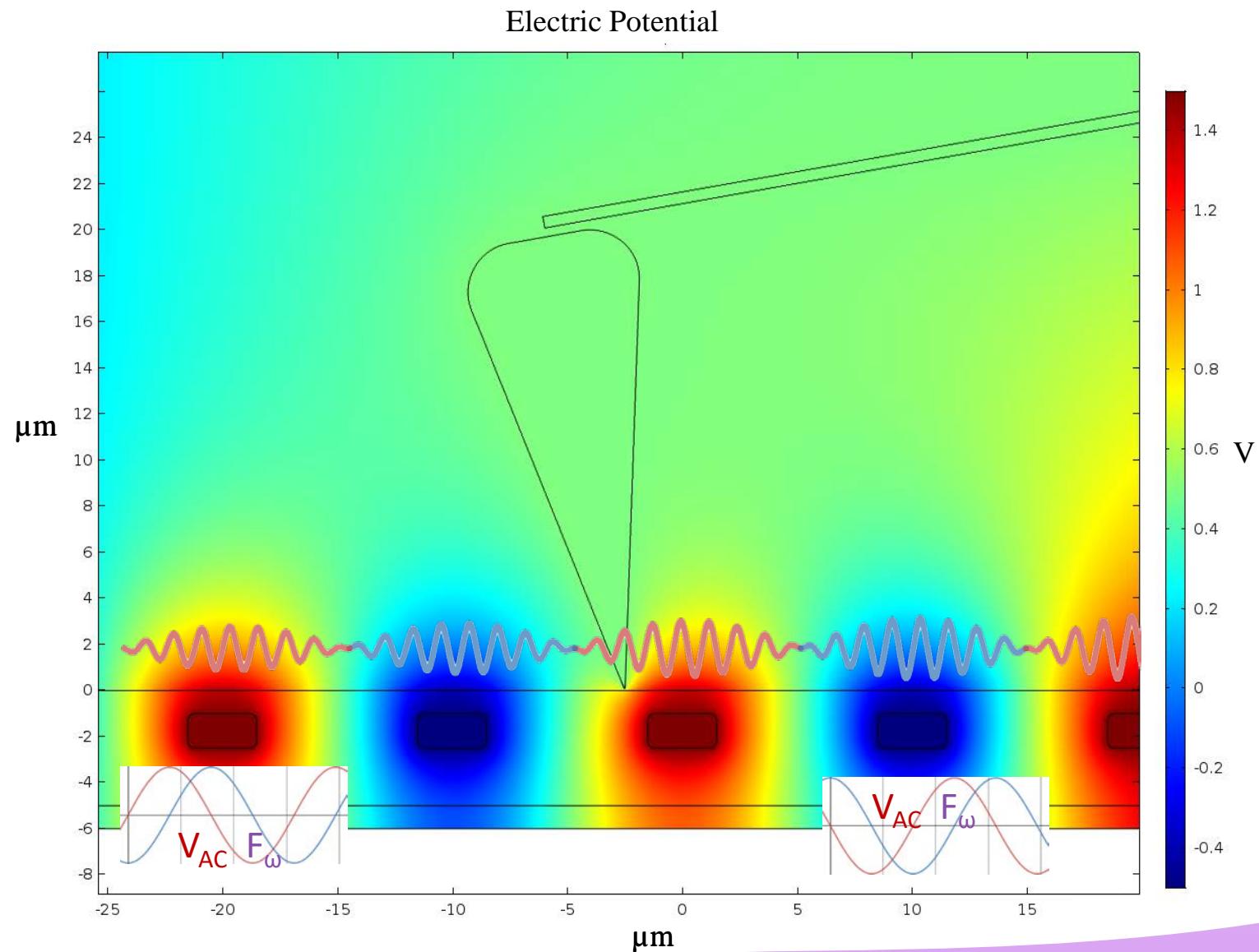
~~Atomic~~ Force Microscopy

Electrostatic[^]



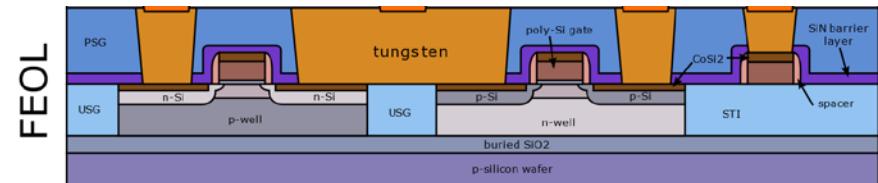
Remote Bias

Electrostatic Force Microscopy

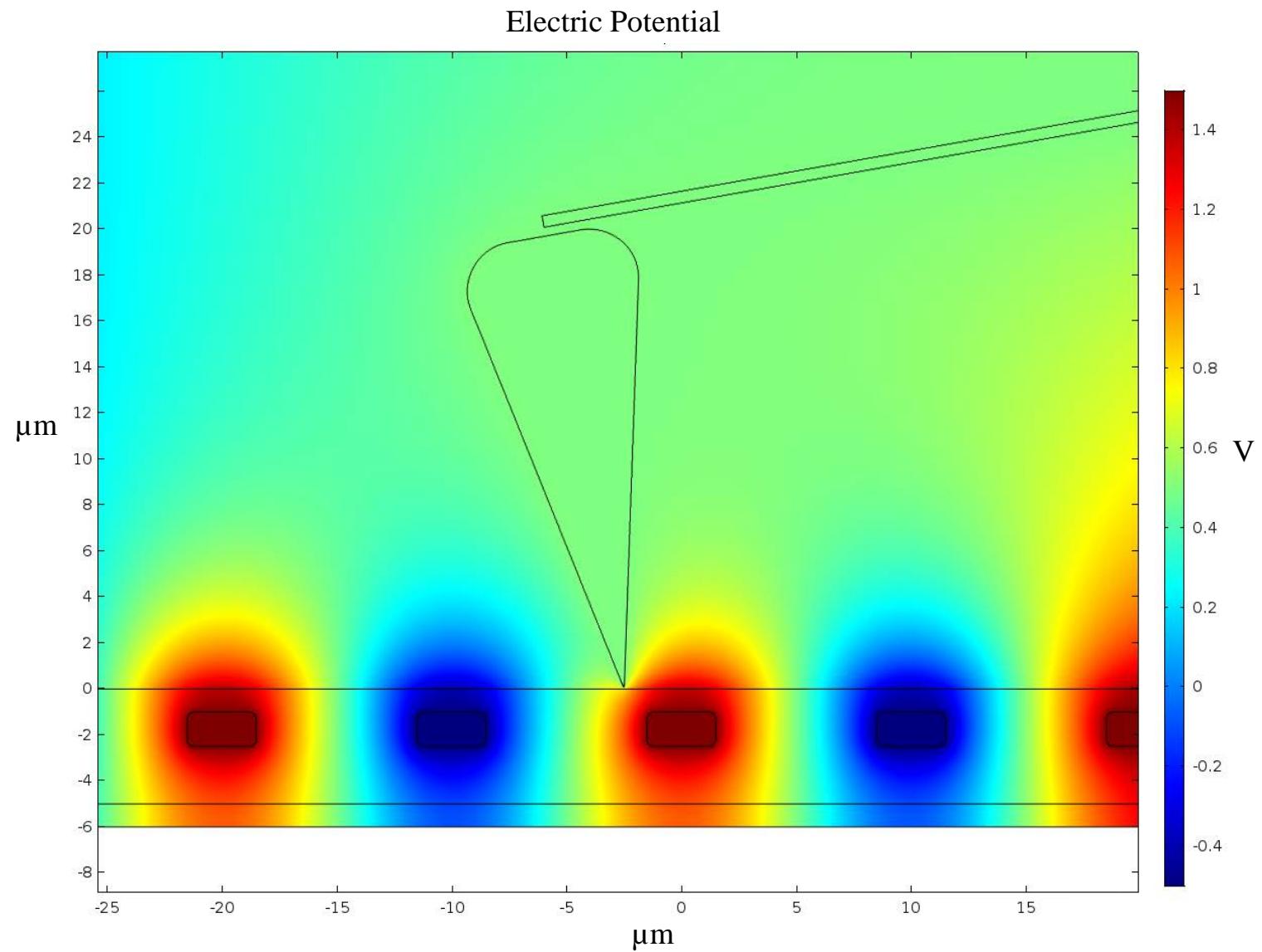


Motivation and Goals

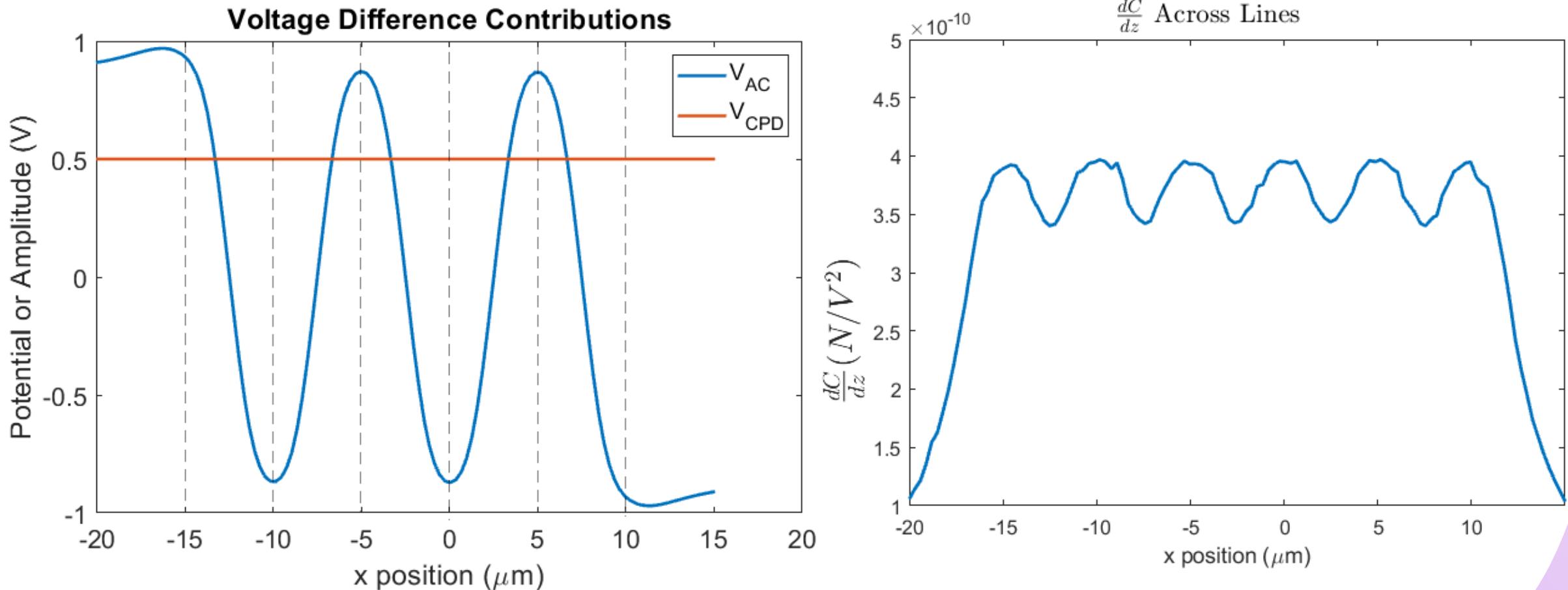
- Back End of Line Testing
- Tip characterization
- Standard Structure



Computational Work

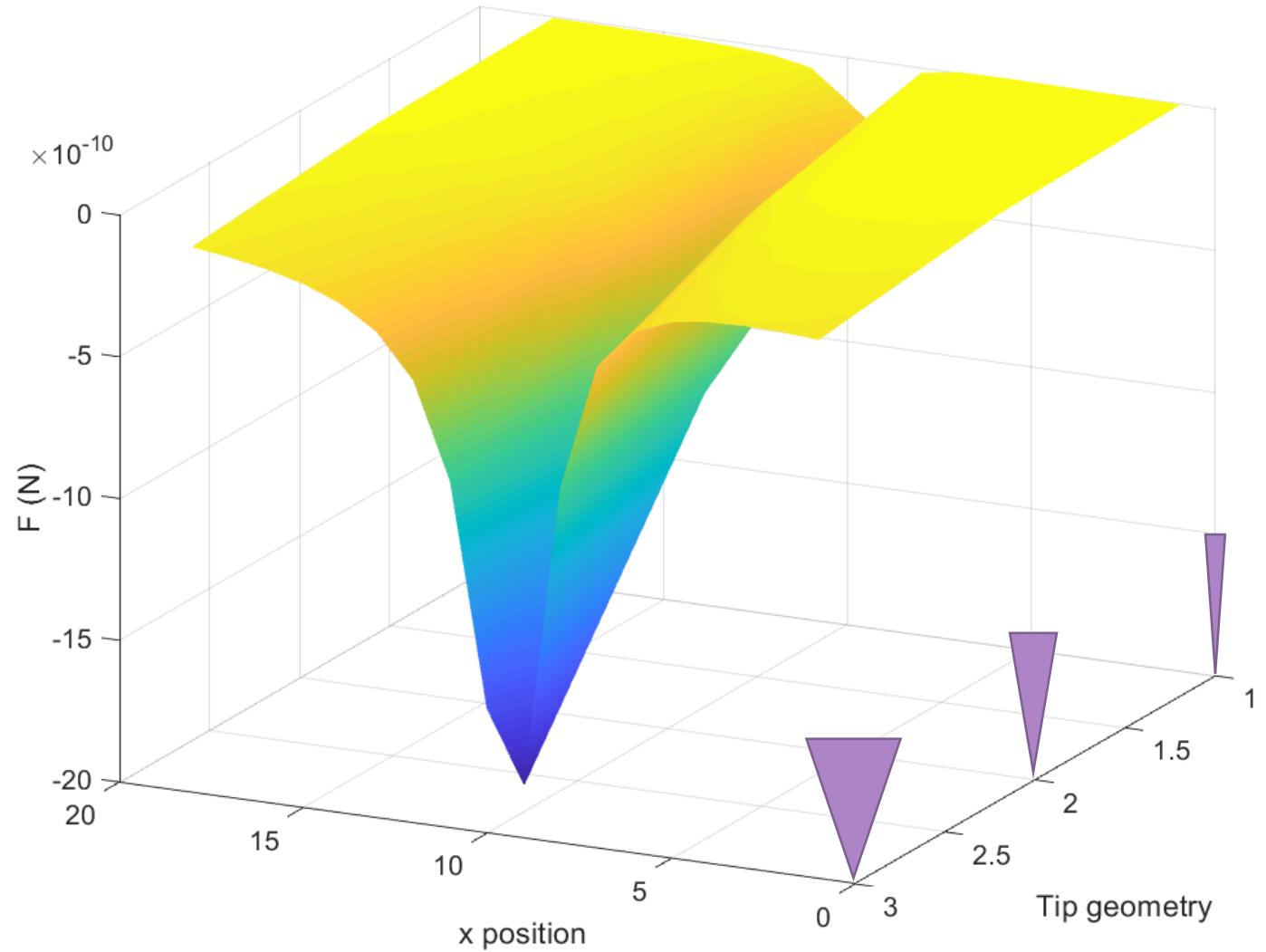


Extracted Values

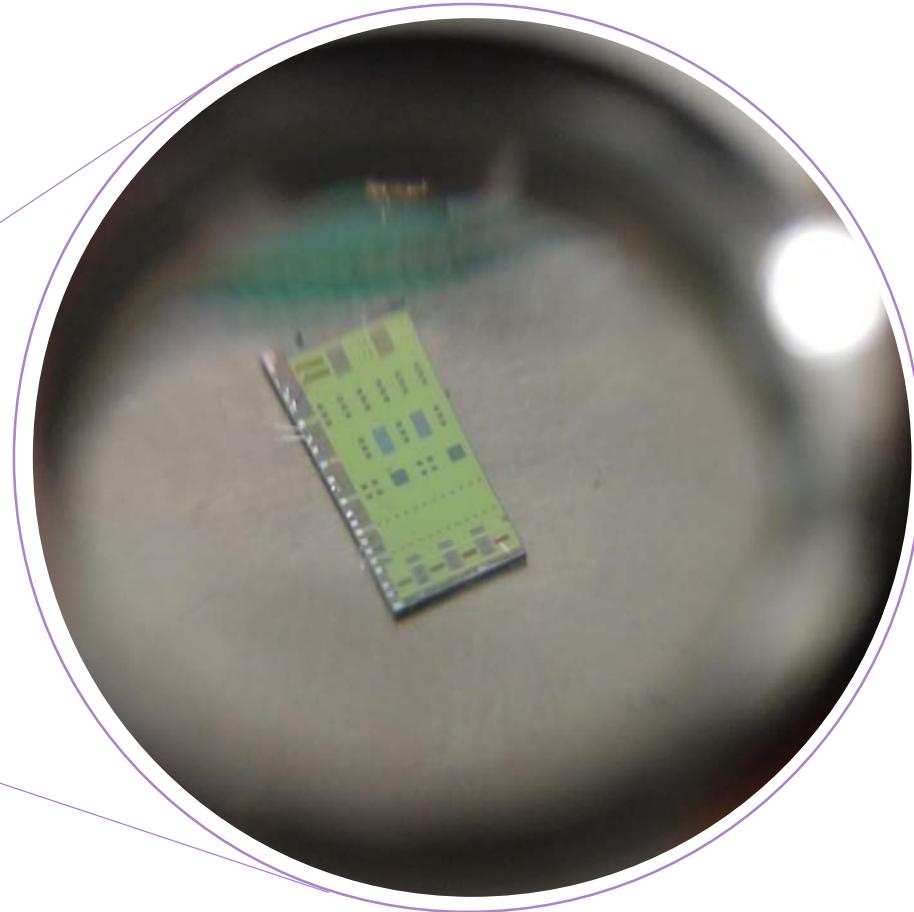
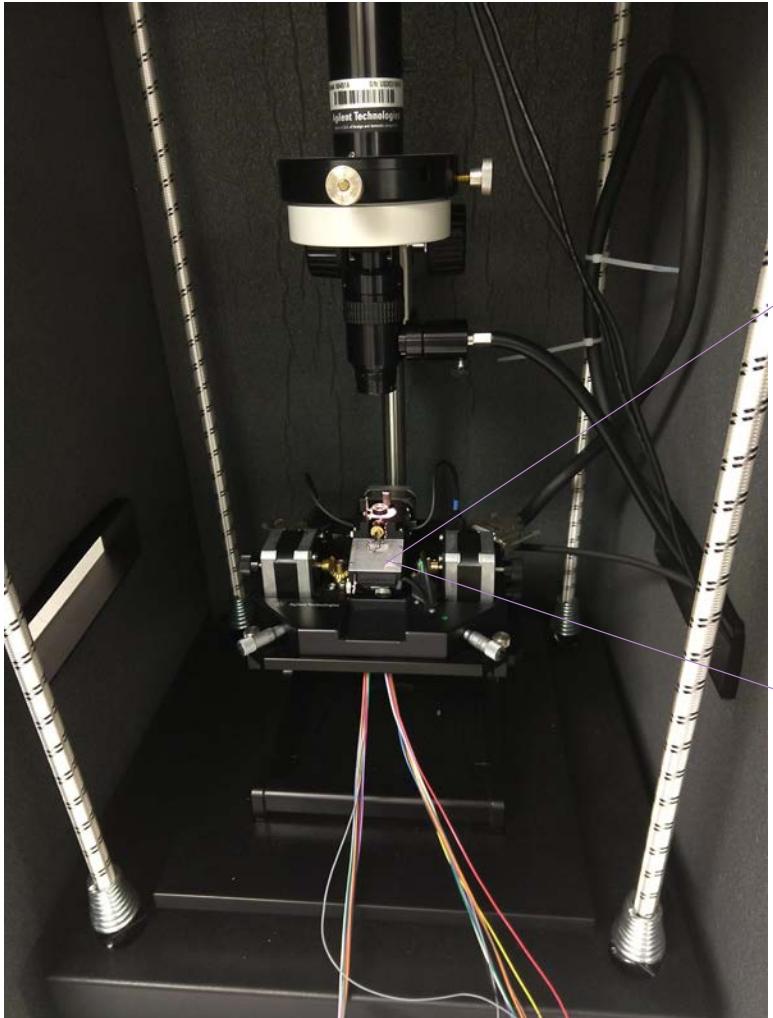


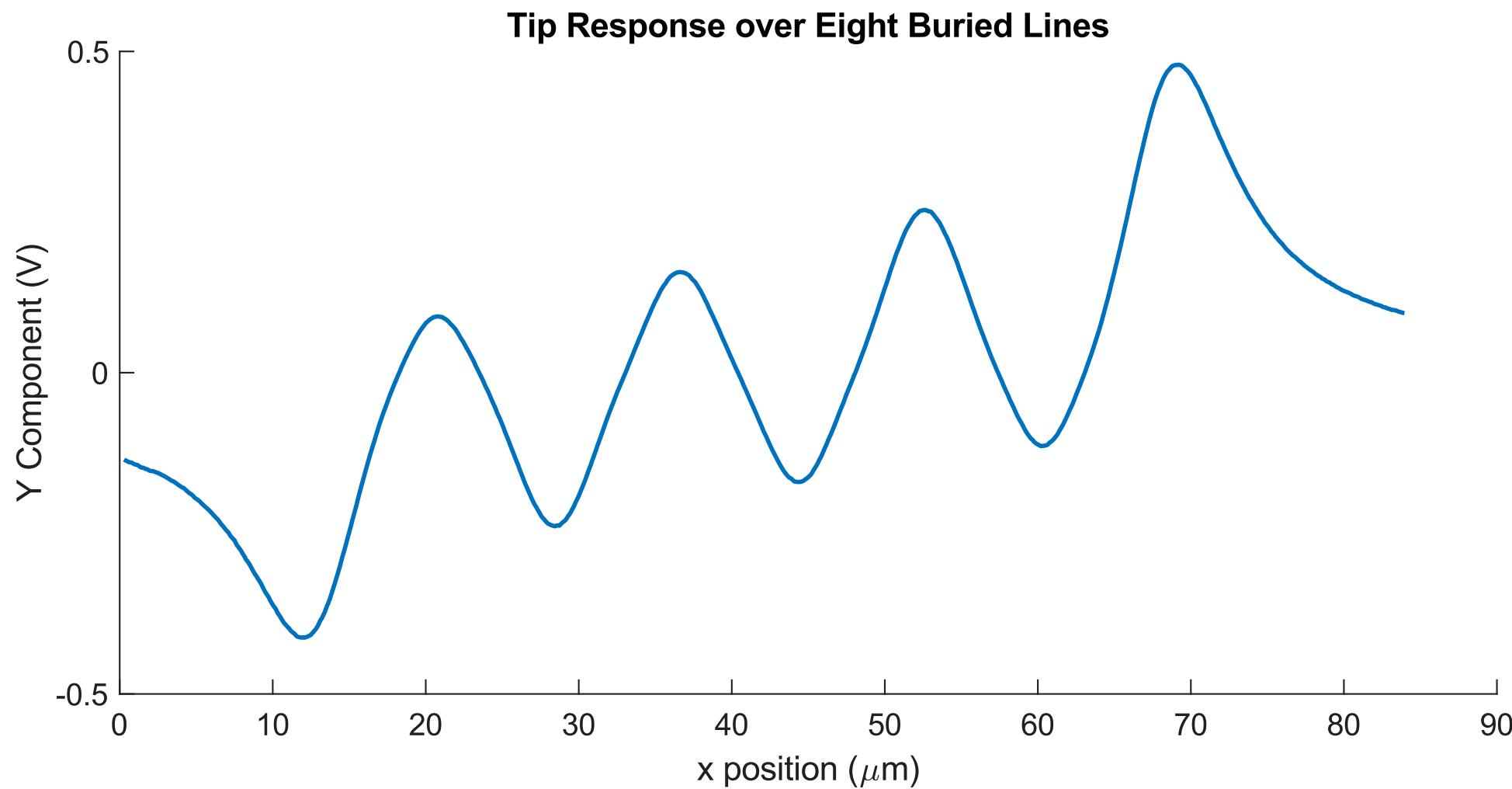
$$F(z, t) = -\frac{1}{2} [(V_{CPD} - VD_c) + V_{AC}\sin(\omega t)]^2 \frac{dC(z)}{dz}$$

Theory's Limitations



Experimental Work





Conclusion

- Theory and modeling
- Instrumentation documentation
- RB-EFM Demonstrated

Acknowledgements

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References:

Melitz, W., Shen, J., Kummel, A. C. & Lee, S. Kelvin probe force microscopy and its application. *Surface Science Reports* **66**, 1-27 (2011).

You L., Ahn J-J, Hitz E., Michelson J., Obeng Y. and Kopanski J. Electromagnetic field test structure chip for back end of line metrology. *Int. Conf. on Microelectronic Test Structures* **235-9** (2015).

